

# Resource Summary Report

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## Oxford: PlasmaPro 800 RIE Plasma Technology

RRID:SCR\_020398

Type: Tool

### Proper Citation

Oxford: PlasmaPro 800 RIE Plasma Technology (RRID:SCR\_020398)

### Resource Information

**URL:** <https://plasma.oxinst.com/products/rie/plasmapro-800>

**Proper Citation:** Oxford: PlasmaPro 800 RIE Plasma Technology (RRID:SCR\_020398)

**Description:** PlasmaPro 800 offers solution for reactive ion etching processes on large wafer batches and 300mm wafers, in compact footprint, open loading system. Large wafer platen allows for production scale batch processing and 300mm wafer handling.

**Resource Type:** instrument resource

**Keywords:** Oxford, Plasma Technology, Instrument, Resource equipment, Equipment, USEDit,

**Availability:** Commercially available

**Resource Name:** Oxford: PlasmaPro 800 RIE Plasma Technology

**Resource ID:** SCR\_020398

**Alternate IDs:** Model\_Number\_800\_RIE

**Record Creation Time:** 20220129T080350+0000

**Record Last Update:** 20260829T182654+0000

### Ratings and Alerts

No rating or validation information has been found for Oxford: PlasmaPro 800 RIE Plasma Technology.

No alerts have been found for Oxford: PlasmaPro 800 RIE Plasma Technology.

### Data and Source Information

**Source:** [SciCrunch Registry](#)

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## Usage and Citation Metrics

We have not found any literature mentions for this resource.